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LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT		Applicant: Josef Böck et al.		
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U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Date	Name	Class	Sub Class	Filing Date If Appropriate
SWL	4,437,897	03/1984	Kemlage			
	5,049,964	09/1991	Sakai et al.			
	5,407,857	04/1995	Higuchi			
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SWL	0 646 952	04/1995	EPO			Yes
SWL	00/13206	08/1999	PCT			Yes
SWL	2004/008543	01/2004	PCT			Yes

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

SWL	Lurng Shehng Lee et al., "Argon Ion-Implantation on Polysilicon or Amorphous-Silicon for Boron Penetration Suppression in p + p MOSFET" August 1998, IEEE Transactions on Electron Devices, pgs. 1737-1744.

EXAMINER: CRANE DATE CONSIDERED: 3/2006
 EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.